[ABSTRACT]

According to one aspect of a technique tThe present disclosure, there is provided a substrate processing apparatus including: a substrate retainerinvention provides a configuration provided with: a substrate holding tool having a heat insulating region at a lower portion thereof; a first reaction tube which houses the substrate holding tool therein and which is with open ended at both an upper end and a lower ends thereof; a second reaction tube which has an occluded with a closed upper end and an open lower end; a furnace openingthroat flange part which has a holding section provided with a holder in a first space disposed between the first reaction tube and the second reaction tube; a heater coveringand a heating part which is provided so as to cover the second reaction tube to heatand which is for heating a substrate arranged inplaced on the substrate retainer inholding tool inside the first reaction tube;. Said configuration is further provided with: a first high-reflection member which ishighly reflective structure provided into the heat insulating region and which has a higher infrared reflectance than the heat insulating material; and a second high-reflection member which has a higher infrared reflectance than the insulation material disposed at the holding sectionhighly reflective structure arranged at the holder provided at an upper end of the throatfurnace opening flange part in such a manner as to be provided toand along an inner wall of the second reaction tube at a lower portion ofbelow the second reaction tube in the first space.